

<b>Notice of References Cited</b>	Application/Control No. 10/553,573		Applicant(s)/Patent Under Reexamination DUSSARRAT ET AL.	
	Examiner Elizabeth Burkhart		Art Unit 1792	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2001/0048973	12-2001	SATO et al.	427/255.39
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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#### NON-PATENT DOCUMENTS

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	U	Fessenden et al, An extension of and the Reversibility of the Silylamine-Amine Exchange Reaction, J. Org. Chem, 1961, 26, (11), p. 4638-4641.
	V	Schuh et al, Disilanyl-amines - Compounds comprising the structural unit Si-Si-N, as single-source precursors for plasma-enhanced chemical vapour deposition (PE-CVD) of silicon nitride, Z. anorg. allg. Chem 619 (1993), p. 1347-1352.
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	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.